

Continued Investigations in Carbon-Based Thin Films for Fuel Cells and Batteries

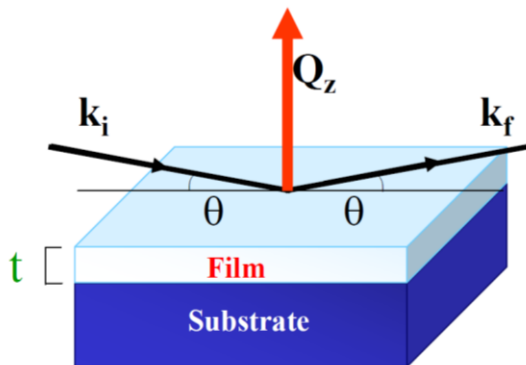
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Carbon Film Background

- Nafion has shown lamellar interface structures when grown on SiO_2 , but not when grown on Au or Pt
- In Hydrogen Fuel Cell PEMs, Nafion grows on Carbon-black, which is too rough for reflectometry
- This is an attempt to grown thin, smooth carbon layers and characterize the Nafion interfaces that might exist in PEMs.

Specular Reflectometry



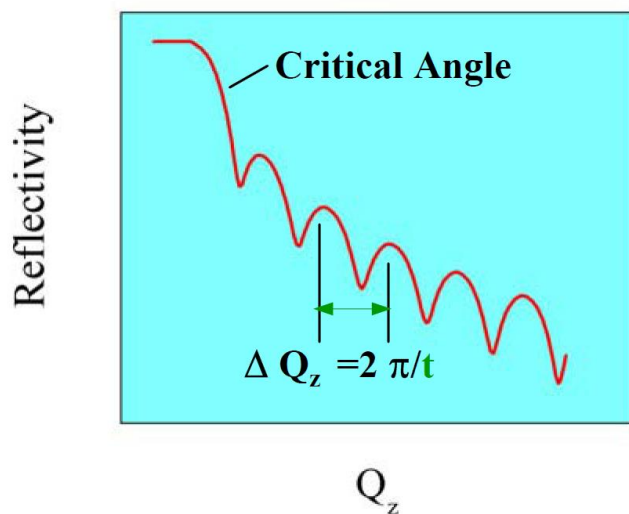
- Specular Reflectometry measures Reflected Intensity vs. grazing angle θ or Q_z with $\theta_i = \theta_f$

$$Q_z = 4\pi \sin \Theta / \lambda$$

- XRR and NR Provide Depth Profile of the SLD
- SLD is related to Composition, and is proportional to the scattering lengths of the elements $Z(i)$

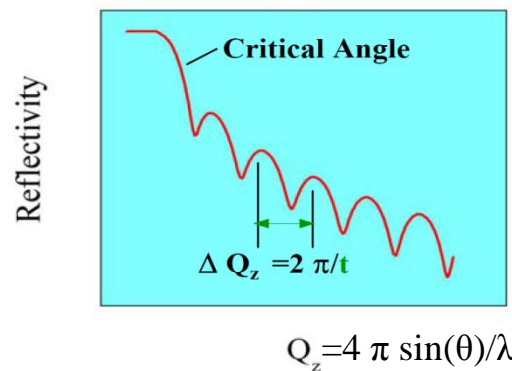
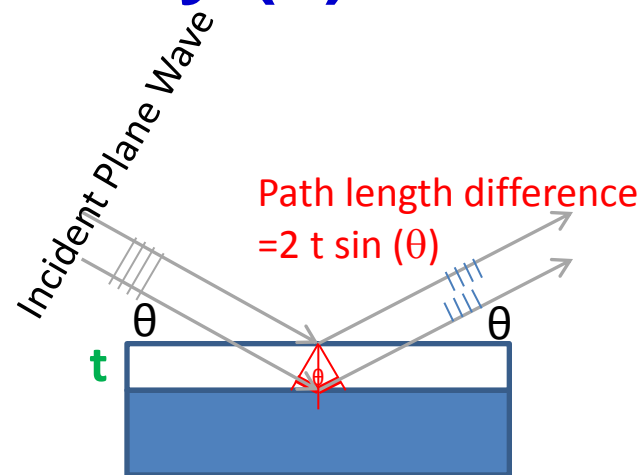
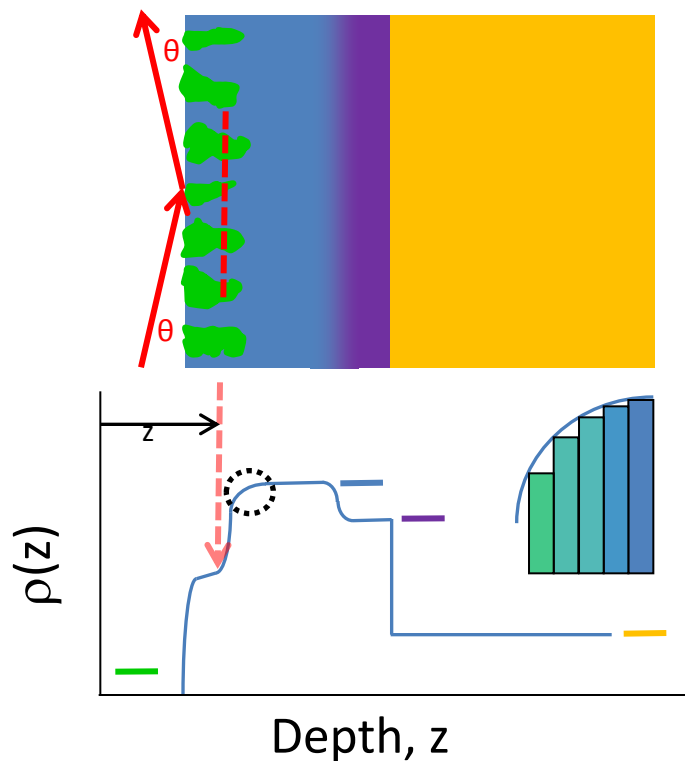
$$SLD(x) = \sum_i Z(i) n_i(x)$$

- Averages SLD in the plane perpendicular to x
- Critical Edge due to total external reflection
- Oscillations with period $2\pi / \text{layer thickness}$
- Additional layers cause additional beating patterns



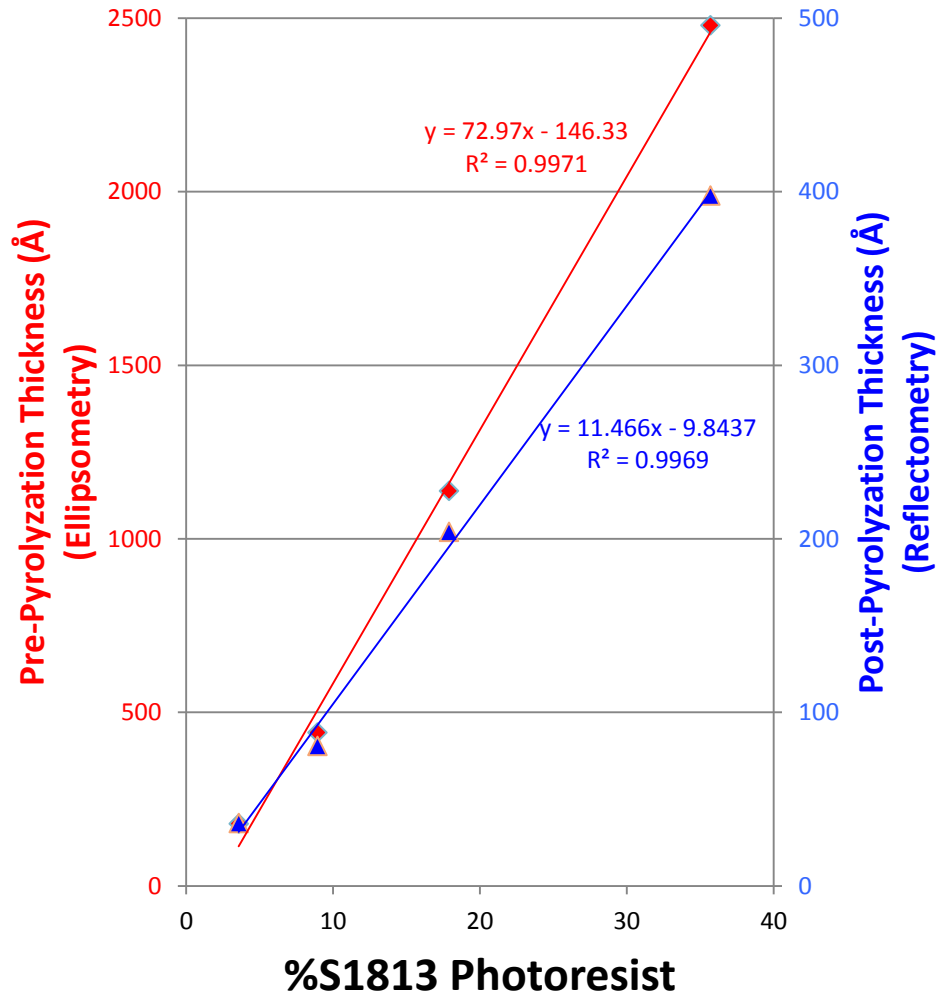
Specular Reflectometry (2)

- One can calculate the reflectivity from the SLD, but not invert the reflectivity since phase information is not measured
- Therefore we must fit the data to models

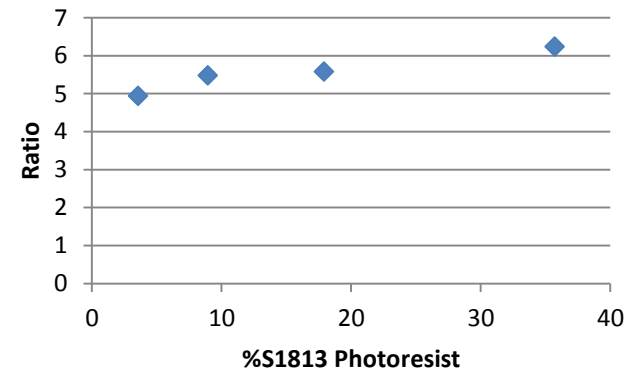


- Reflectometry averages the SLD of materials in the plane
- Gradients can be approximated by a set of uniform slabs
- Can determine the ratio of two known components

Post Pyrolyzation Thickness vs. Concentration

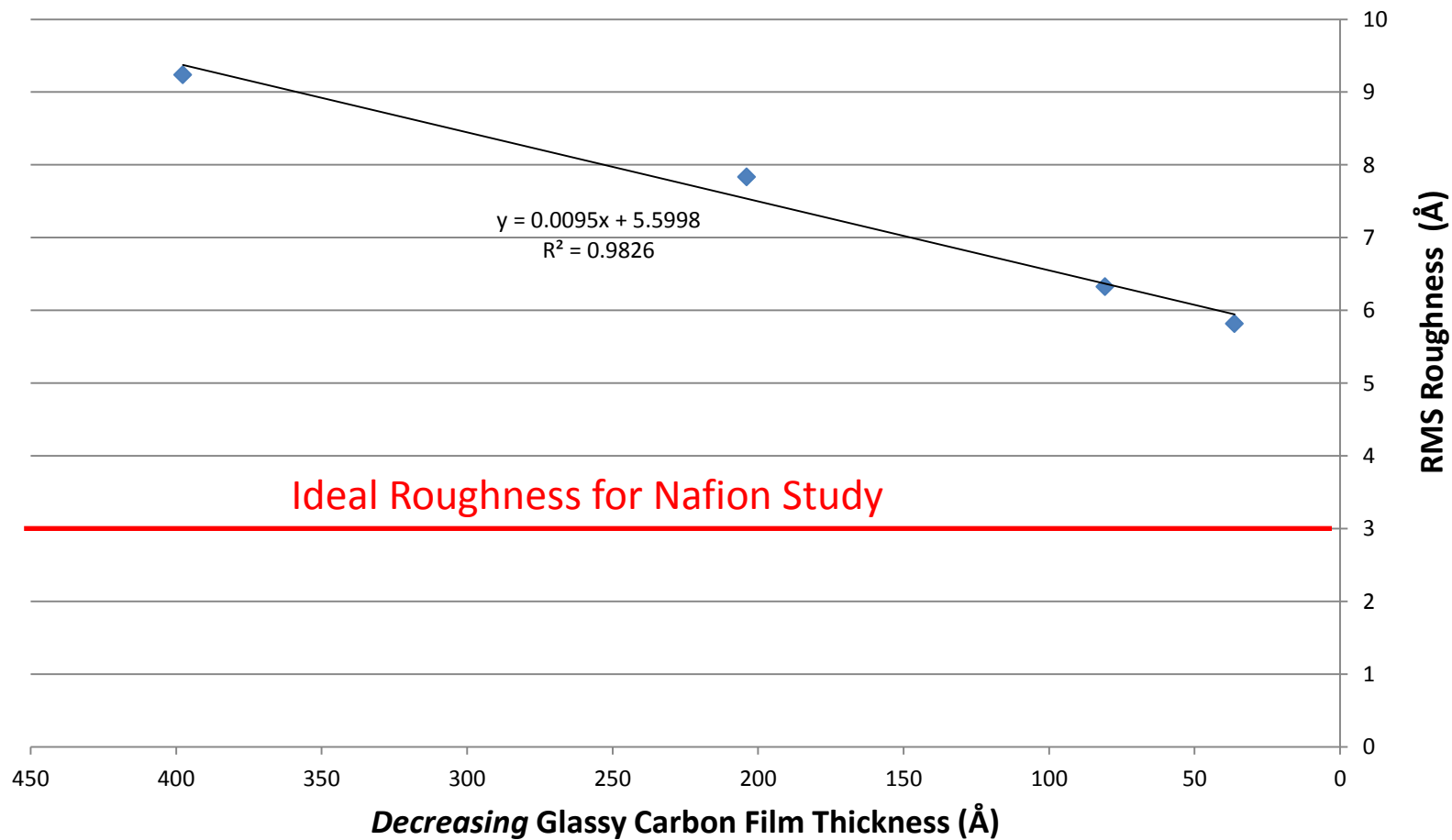


Ratio of Pre-Pyrolyzation Thickness to Post-Pyrolyzation Thickness



RMS Roughness vs. Film Thickness

Roughness decreases with decreasing thickness



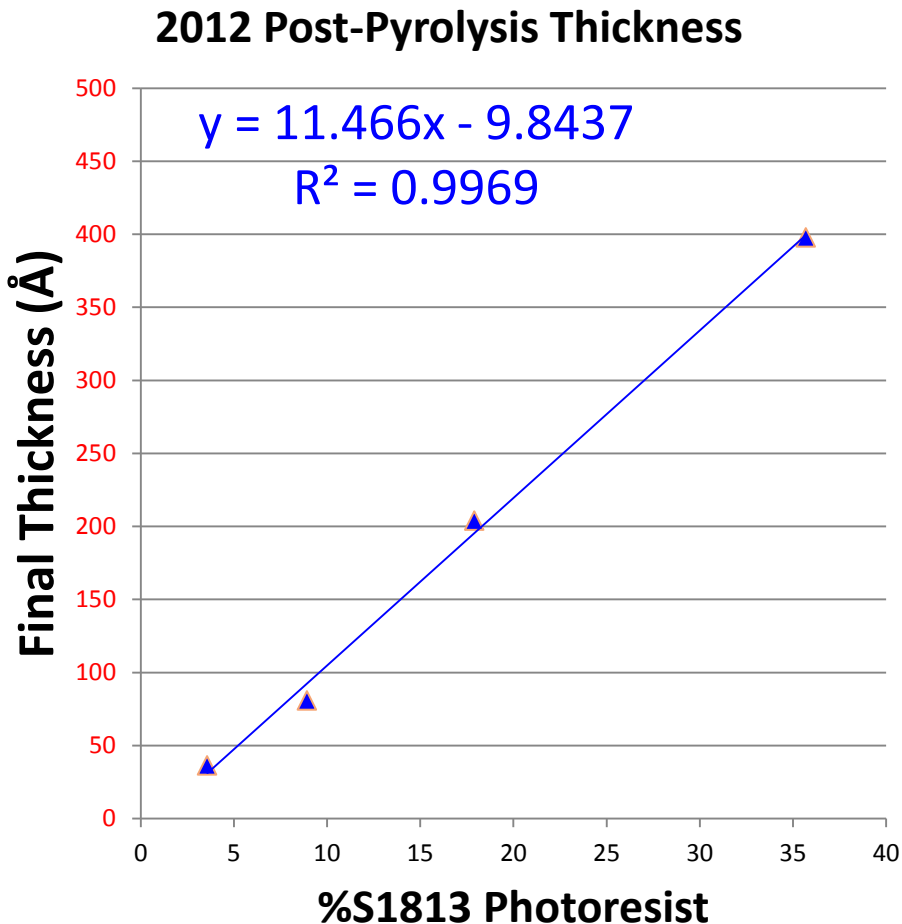
Previous Pyrolyzed Photoresist Thicknesses based on Concentration

Sample #	%S1813	Desired Prepyrolysis Thickness (Å)	Measured PrePyrolysis Thickness (Ellipsometry)	Desired Final Thickness	Measured Final Thickness (X-Ray Reflectometry)
1	35.7	5000	2479	1000	398
2	17.9	2500	1138	500	204
3	8.93	1250	442	250	80.7
4	3.57	500	179	100	36.2

2013 Glassy Carbon Film Preparation

- Use 2012 data to determine photoresist concentrations needed to achieve 2 target film thicknesses: 30 Å and 50 Å
- Mix 2 different concentrations of S1813 Photoresist diluted in PGMEA
- Spin Coat each concentration on 2 thick and 2 thin wafers at 3500 rpm for 45sec
- Soft bake half of the samples overnight
- Pyrolyze all samples in forming gas (1000°C)
- Analyze all samples using XRR and pick most suitable for Nafion investigation
- Spin coat Nafion layer on thin carbon film
- Use XRR and NR in multiple environments to characterize the Nafion/Carbon film interface

Determining 2013 Photoresist Concentrations



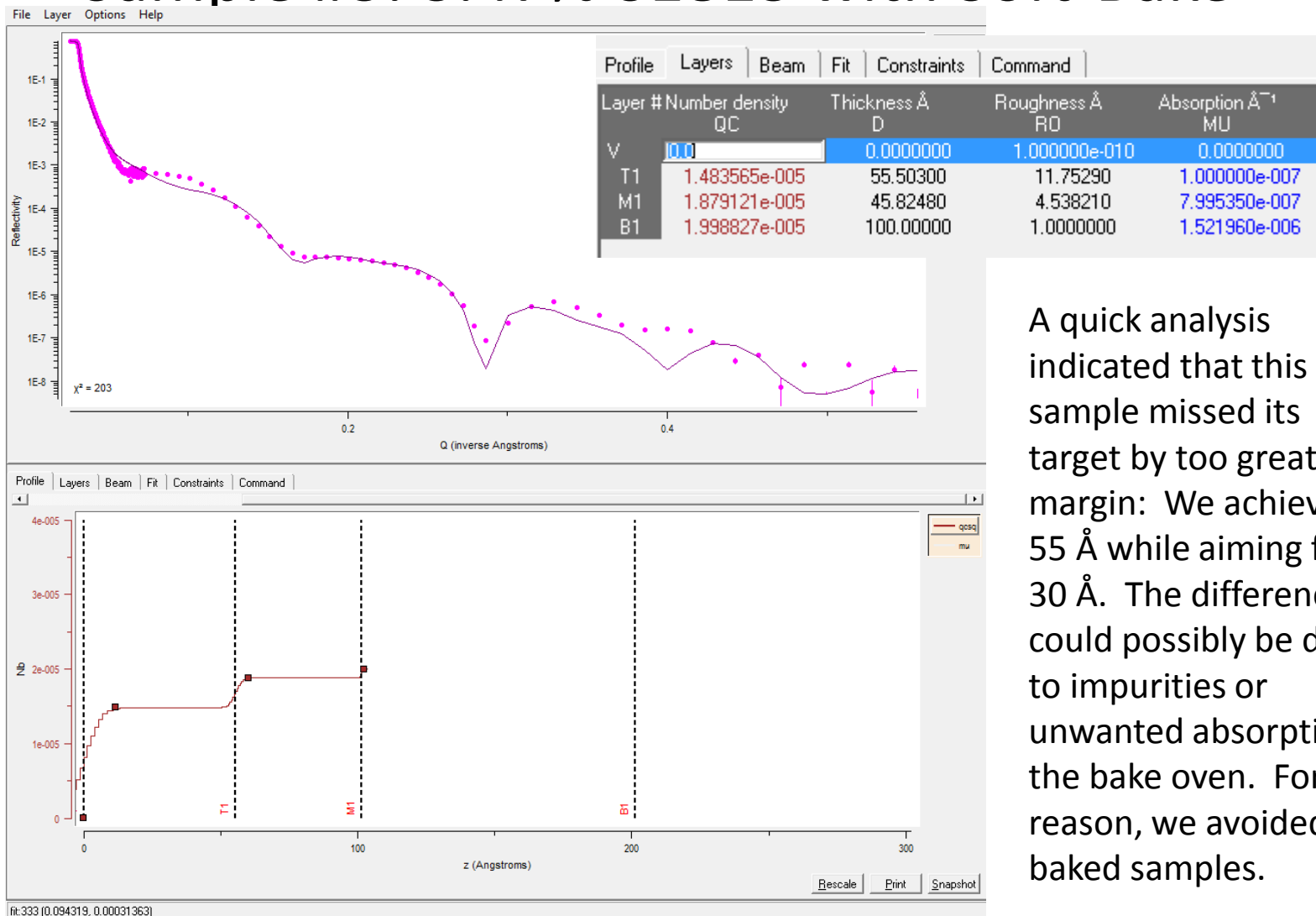
By entering the target thicknesses of 30 Å and 50 Å into the best fit equation, we determine S1813 concentrations of 3.47% and 5.22%.

Slide Preparation

- First, dilute S1813 to 10% in PGMEA (1 mL S1813 + 9 mL PGMEA = 10 mL solution)
- Adjust to final concentrations
 - 3.47% = 3.47 mL of 10% + 6.53 mL of PGMEA
 - 5.22% = 5.22 mL of 10% + 4.78 mL of PGMEA
- Spin-coat all labeled slides at 3500 rpm for 45 seconds
- Soft-bake half of all samples (1b, 2, 3, & 5) at 200° C overnight
- Have all samples pyrolyzed in forming gas at CNST.
- Because of time constraints, perform quick XRR to see which sample has ideal thickness for Nafion study.
(These were only done for thick wafers; thin wafers are available for follow-up/further study)

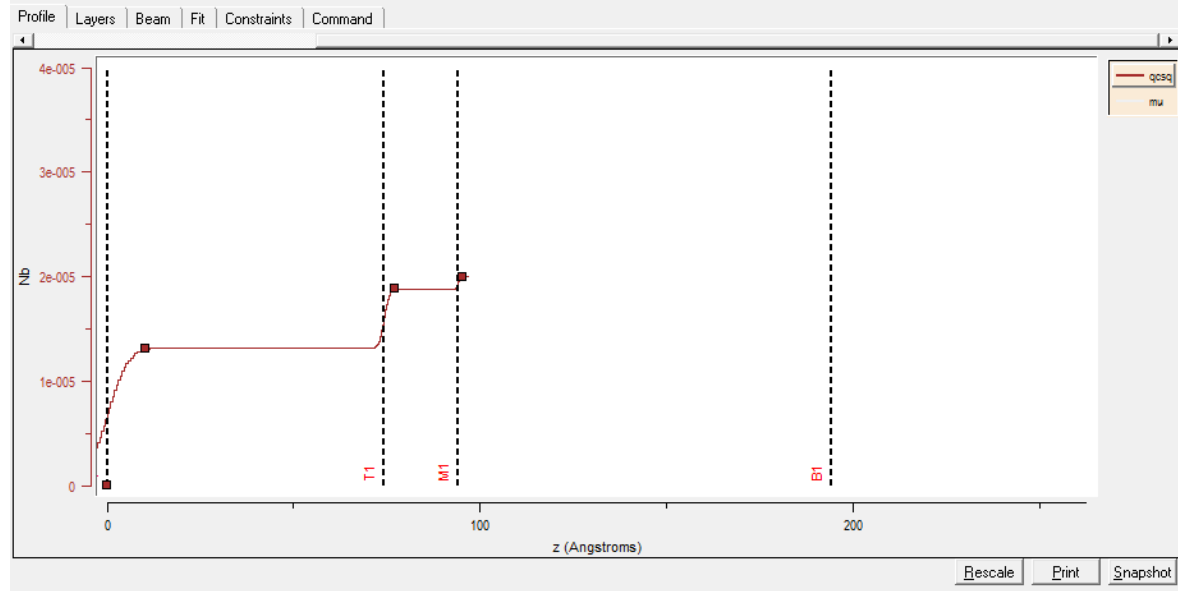
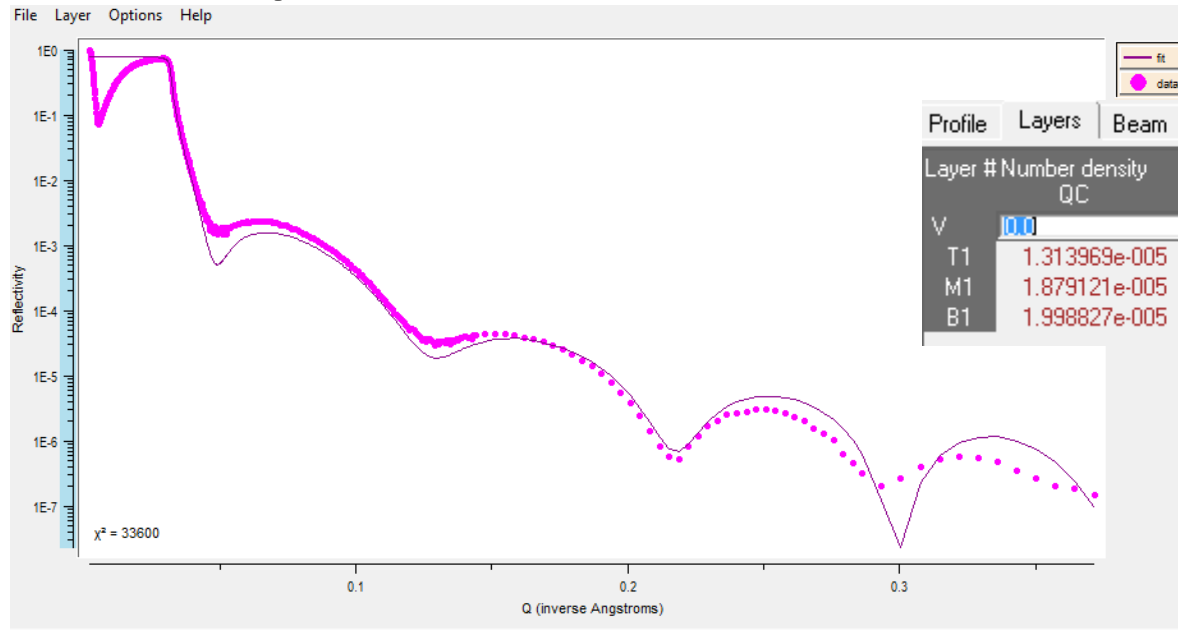
Preliminary Results

- Sample #3: 3.47% S1813 with Soft-Bake



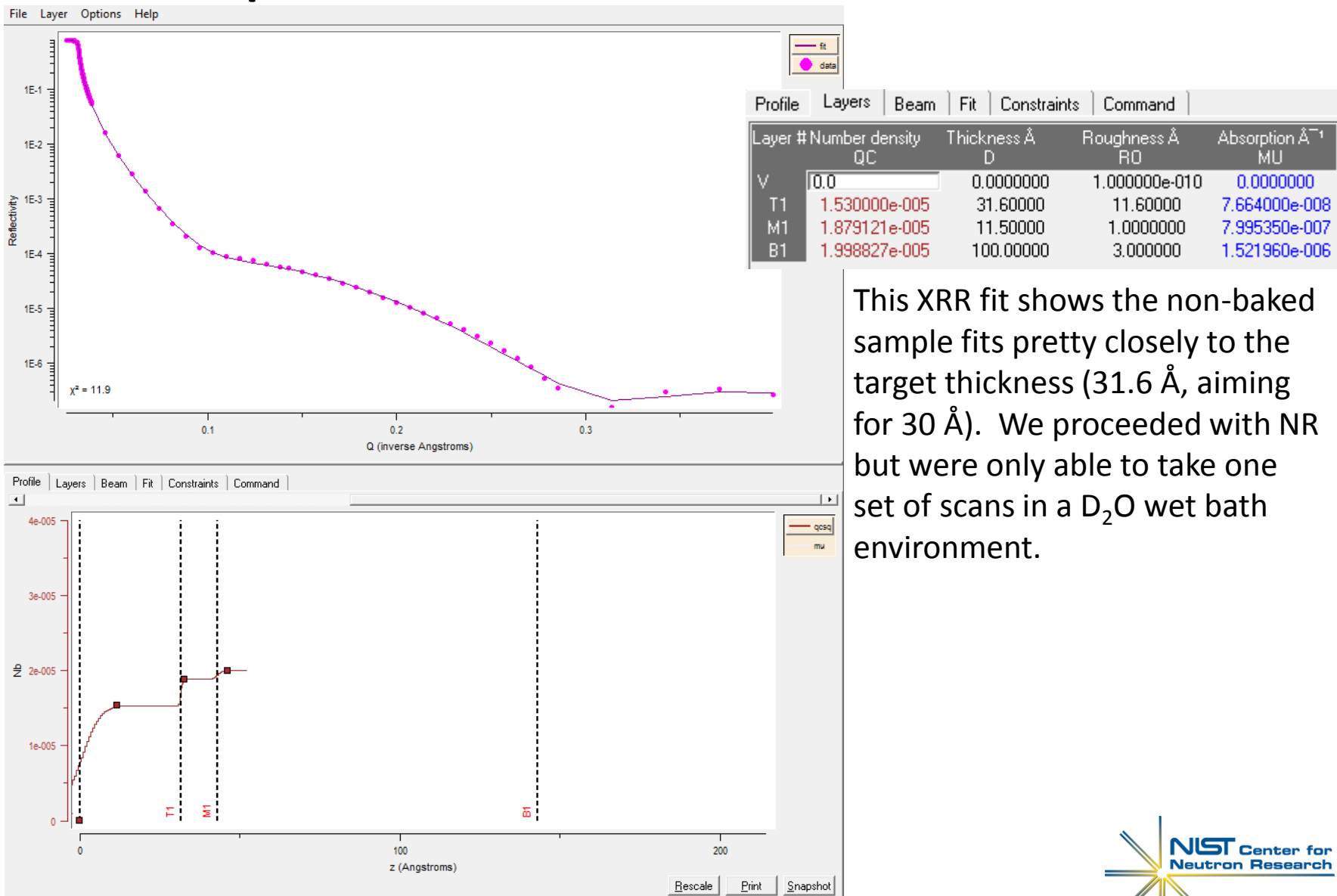
A quick analysis indicated that this sample missed its target by too great a margin: We achieved 55 Å while aiming for 30 Å. The difference could possibly be due to impurities or unwanted absorption in the bake oven. For this reason, we avoided baked samples.

Sample #5: 5.22% S1813; Soft-Bake



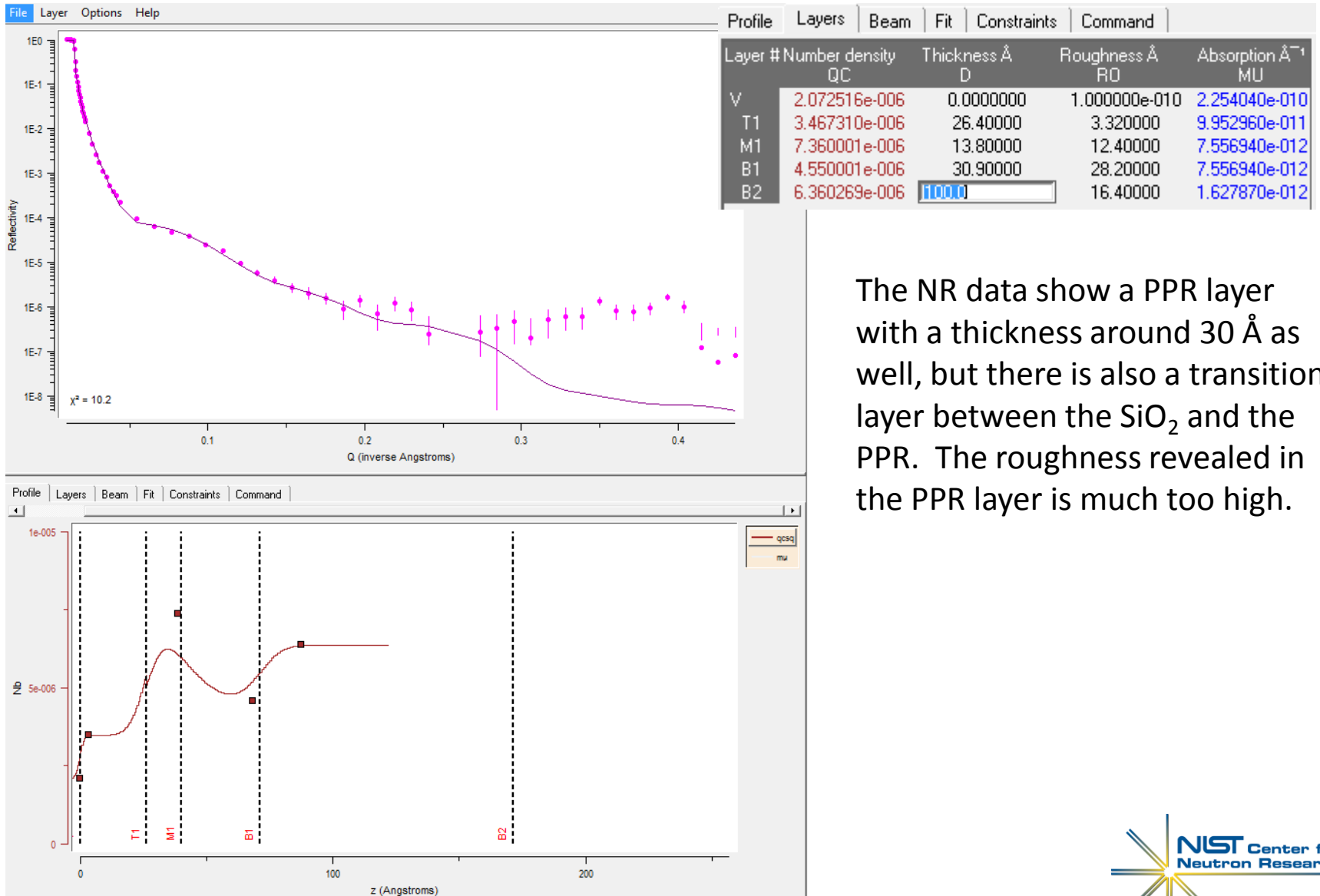
Here again we see an overshoot of desired thickness (74 Å instead of 50 Å). This is outside the range of desired thickness and also probably contains unwanted impurities. We pursued analyses of the two unbaked samples: #4 and #25.

Sample #4: 3.47% S1813; No Bake



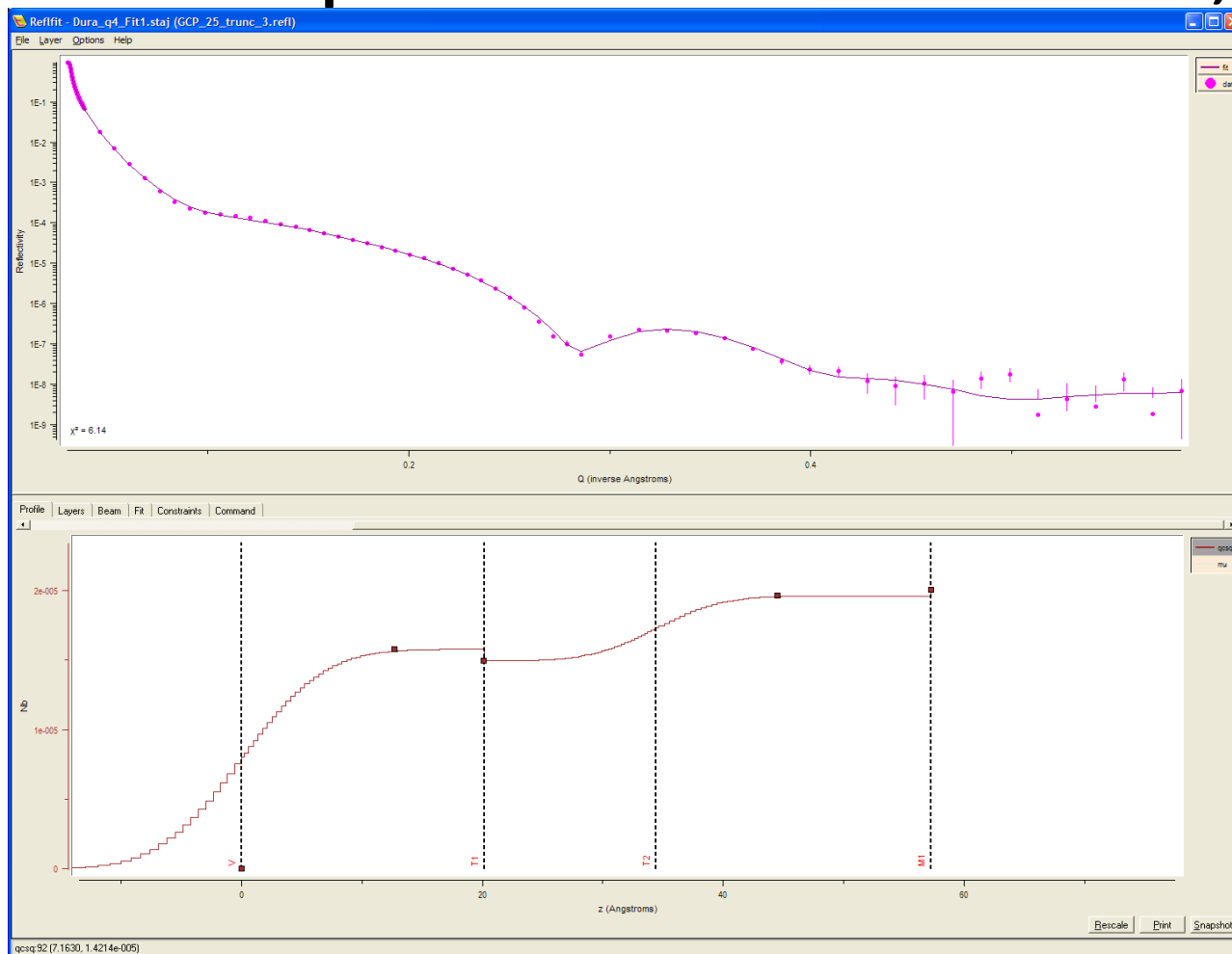
This XRR fit shows the non-baked sample fits pretty closely to the target thickness (31.6 Å, aiming for 30 Å). We proceeded with NR but were only able to take one set of scans in a D₂O wet bath environment.

Sample #4; NR in D₂O Liquid



The NR data show a PPR layer with a thickness around 30 Å as well, but there is also a transition layer between the SiO₂ and the PPR. The roughness revealed in the PPR layer is much too high.

Sample #25: 5.22% S1813; No Bake



The target thickness for the 5.22% solution was 50 Å, but this XR fit indicates a total thickness for the PPR of ~34 Å. We extended the analysis for this sample, using NR in a dry environment and in a 90% RH (D_2O) environment. This was the sample that we put Nafion on for additional NR measurements. (Thanks to Joe Dura for completing this data fit.)

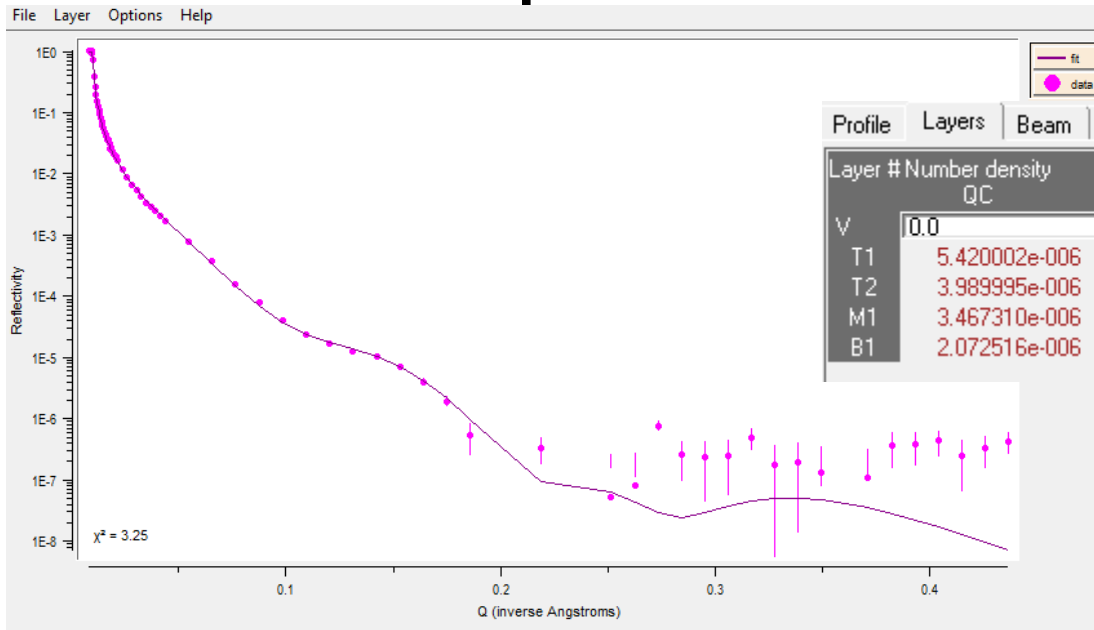
Reffit - Dura_q4_Fit1.staj (GCP_25_trunc_3.refl)

Profile Layers Beam Fit Constraints Command

Layer #	Number density	Thickness Å	Roughness Å	Absorption μ^{-1}
	ρ_c	D	RO	MU
V	0.00	0.000000	1.000000e-010	0.0000000
T1	1.575920e-005	20.13390	12.69600	2.460000e-007
T2	1.492159e-005	14.28720	1.000000e-010	1.230000e-007
M1	1.956333e-005	22.86480	10.08080	7.995350e-007
B1	1.998827e-005	100.00000	1.000000e-010	1.521960e-006

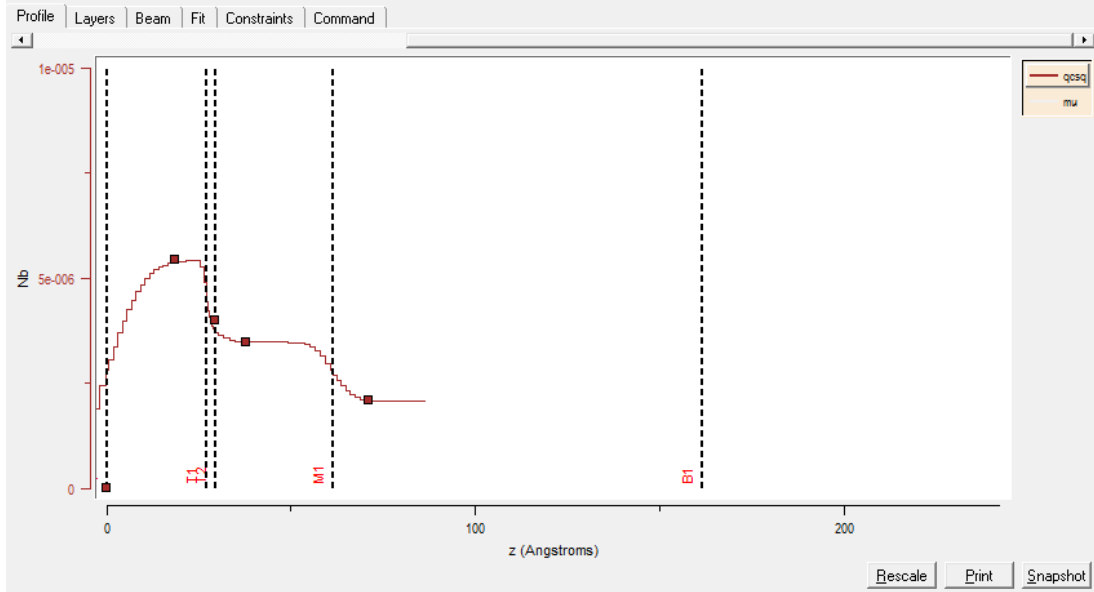


Sample #25: NR in Dry Cell

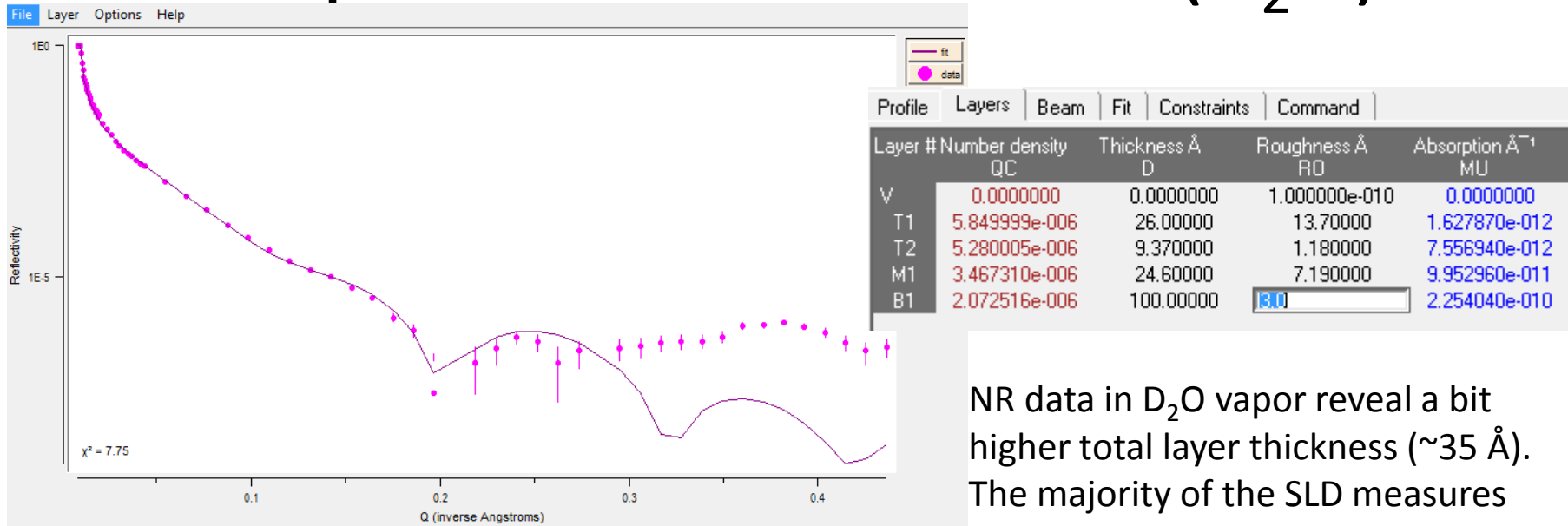


Layer #	Number density	Thickness Å	Roughness Å	Absorption Å ⁻¹
V	QC	D	RO	MU
V	0.0	0.000000	1.000000e-010	0.0000000
T1	5.420002e-006	27.10000	18.60000	7.556940e-012
T2	3.989995e-006	2.561330	2.270000	7.556940e-012
M1	3.467310e-006	31.90000	8.170000	9.952960e-011
B1	2.072516e-006	100.00000	9.630000	2.254040e-010

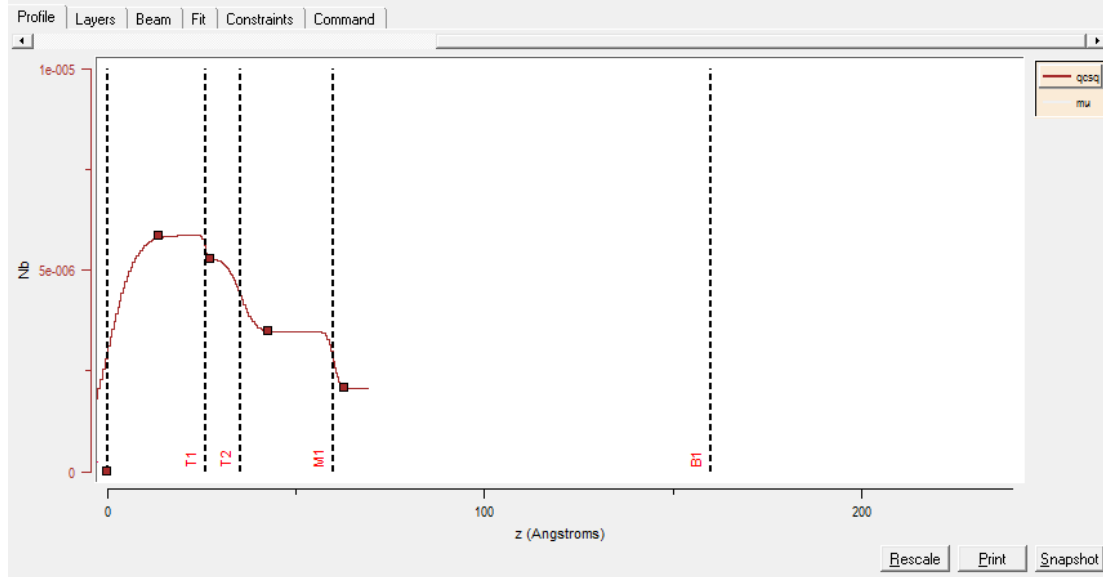
NR data for the same sample fit to a thinner total thickness (~29.7 Å) and greater total roughness.



Sample #25: NR in 90% RH (D₂O)



NR data in D₂O vapor reveal a bit higher total layer thickness (~35 Å). The majority of the SLD measures higher, indicating pores filled with the vapor.

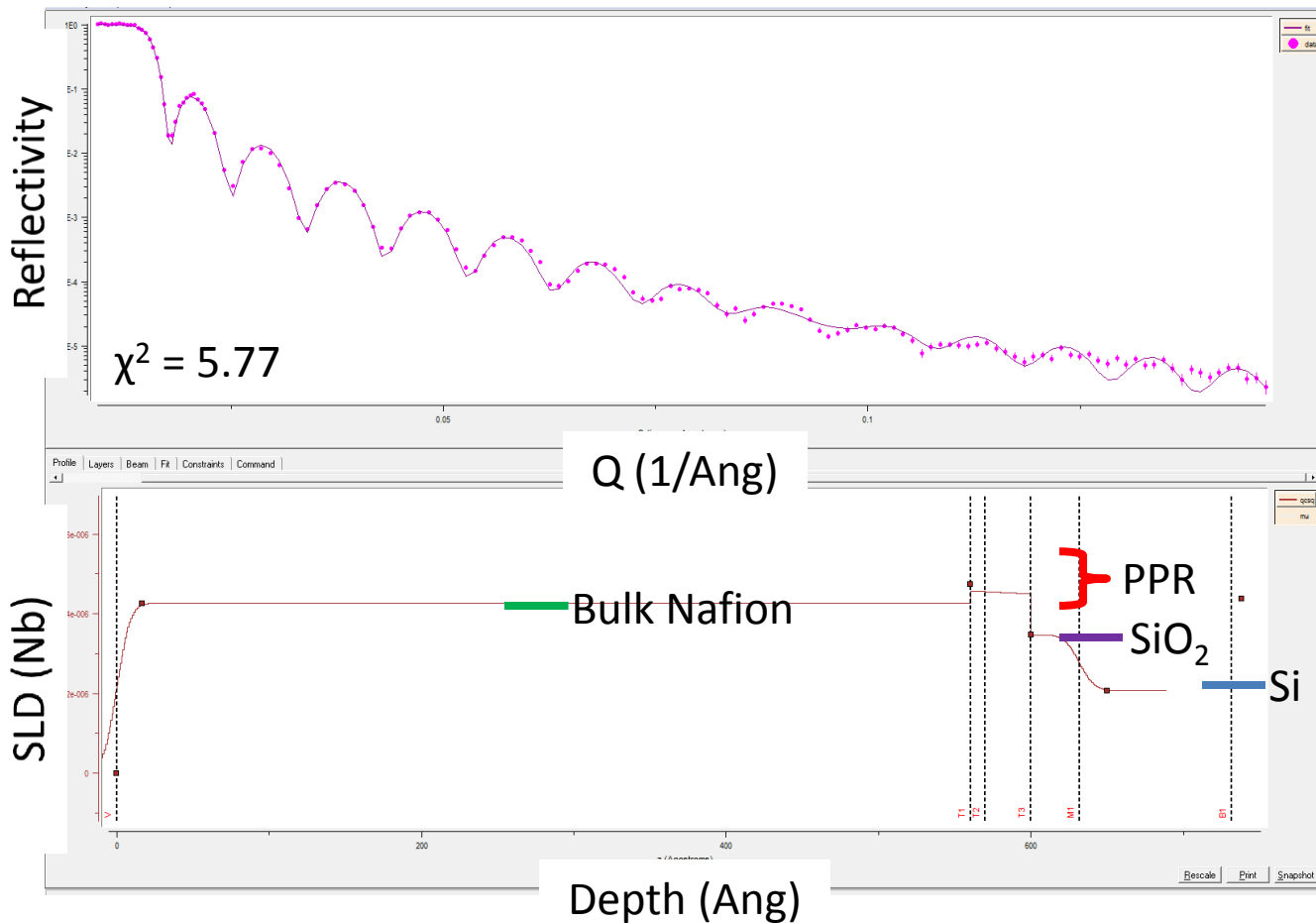


Adding Nafion to Sample #25

- Spin-coat 1:16 solution of Nafion in Ethanol onto sample
- Bake for one hour at 60°C
- Collect NR data in various environments
 - Dry (Argon gas)
 - 90% RH D₂O
 - 90% RH H₂O
- Thanks to Ben Jones for data fits that follow

Fit Neutron Data

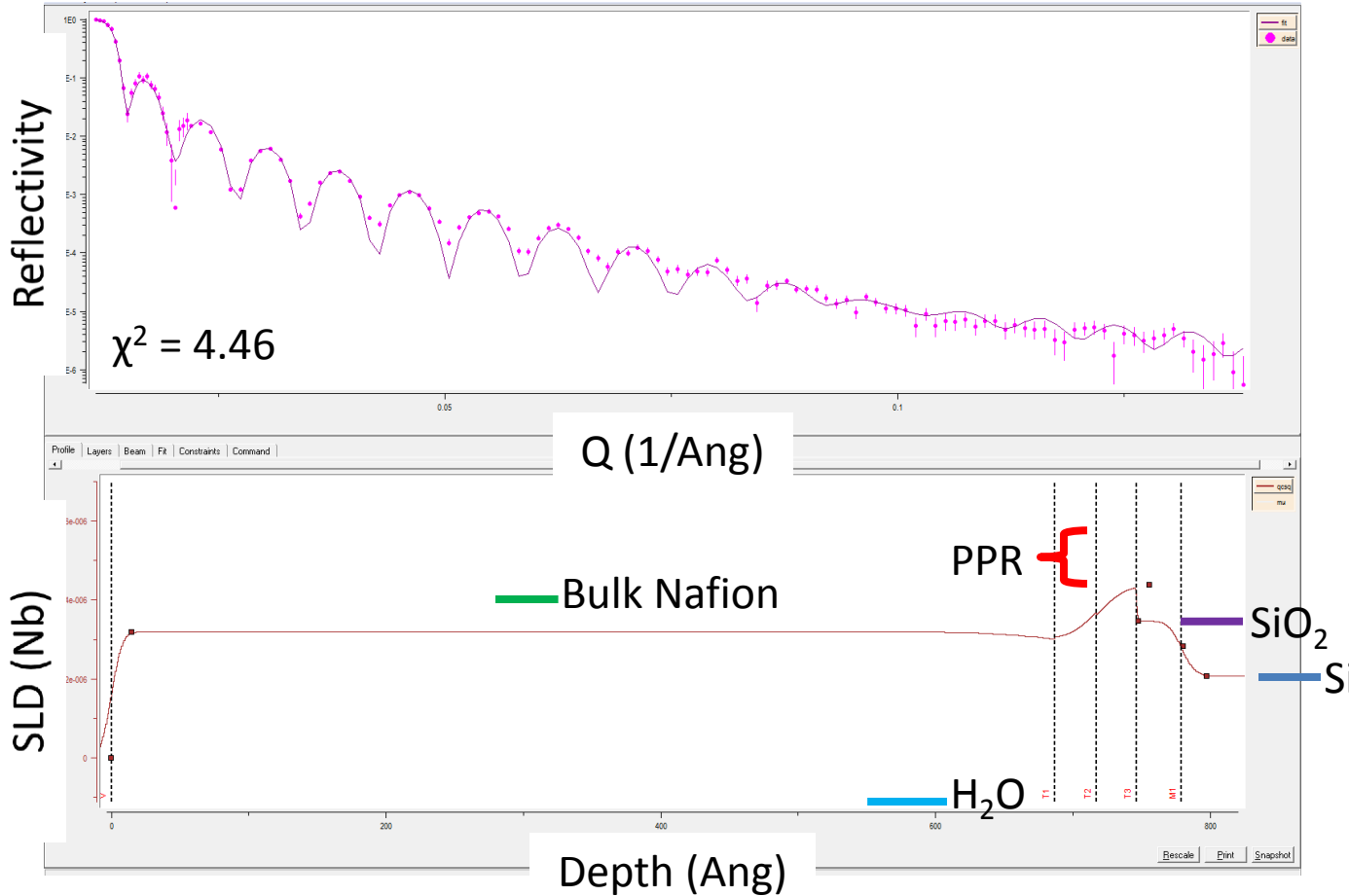
Dry Nafion/PPR



Dry Nafion on PPR reveals a thin layer of high sld under the bulk Nafion with a sharp interface

Fit Neutron Data

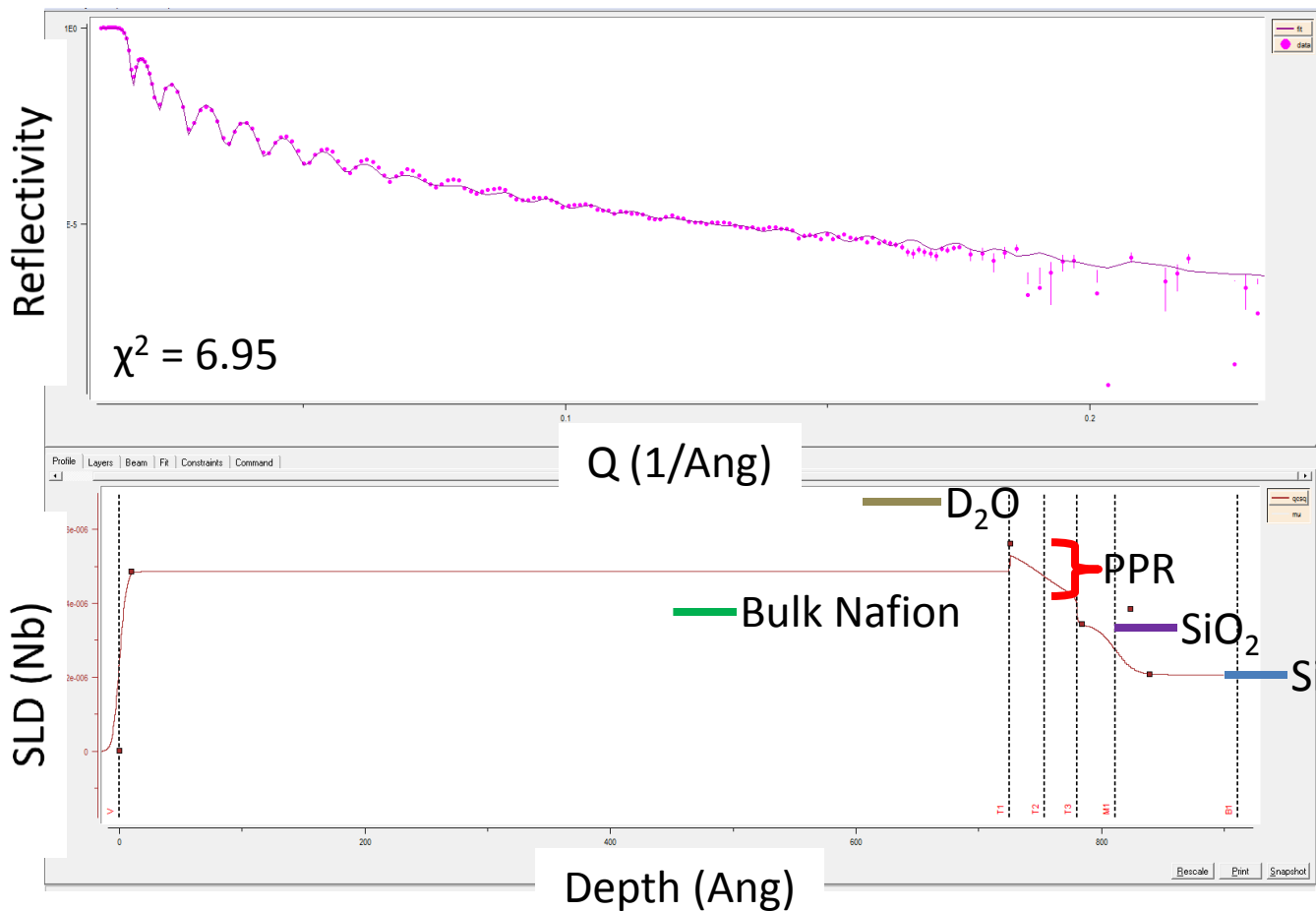
Nafion/PPR in H₂O vapor, RH = 90%



H₂O vapor reveals a strong dip in *sld* between Nafion and the PPR layer, corresponding to a single water-rich layer at the interface

Fit Neutron Data

Nafion/PPR in D₂O vapor, RH = 90%



D₂O reveals a strong peak in sld between the Nafion and PPR layers, also corresponding to a single water-rich layer at the interface

Conclusions

- We did not hit target roughness values with carbon films
- Variations in Nafion SLD in H₂O and D₂O vapor indicate either porosity within the layer or a water-rich layer at the interface with the PPR
- We do not see the lamellae seen on SiO₂
- Simultaneous fitting of two data sets would provide better indicators of layer structures

Next Steps

- Investigate different photoresists or possibly combinations of photoresists to minimize roughness
- Change the pyrolyzation environment to vacuum
- Investigate Nafion on graphene

Simple Scientific Method-Finding Meaning in the World

Observe

- Seek new environments to observe
- Observe your actions/influence on the environment you are observing

Describe

- Observations are limited by language
- Language/knowledge enhance observation

Relate

- It is not science until it is shared with others
- Participating means serving as author and audience

